Supplementary Information

Figure S1: (a) Cyclic voltammetry of WO_3 thin film at different scan rates (20–100 mV/s), and (b) Chronocoulometry (CC) trace of WO_3 thin film.

Table S1: Literature comparison table of EC properties of annealed WO_3 films.

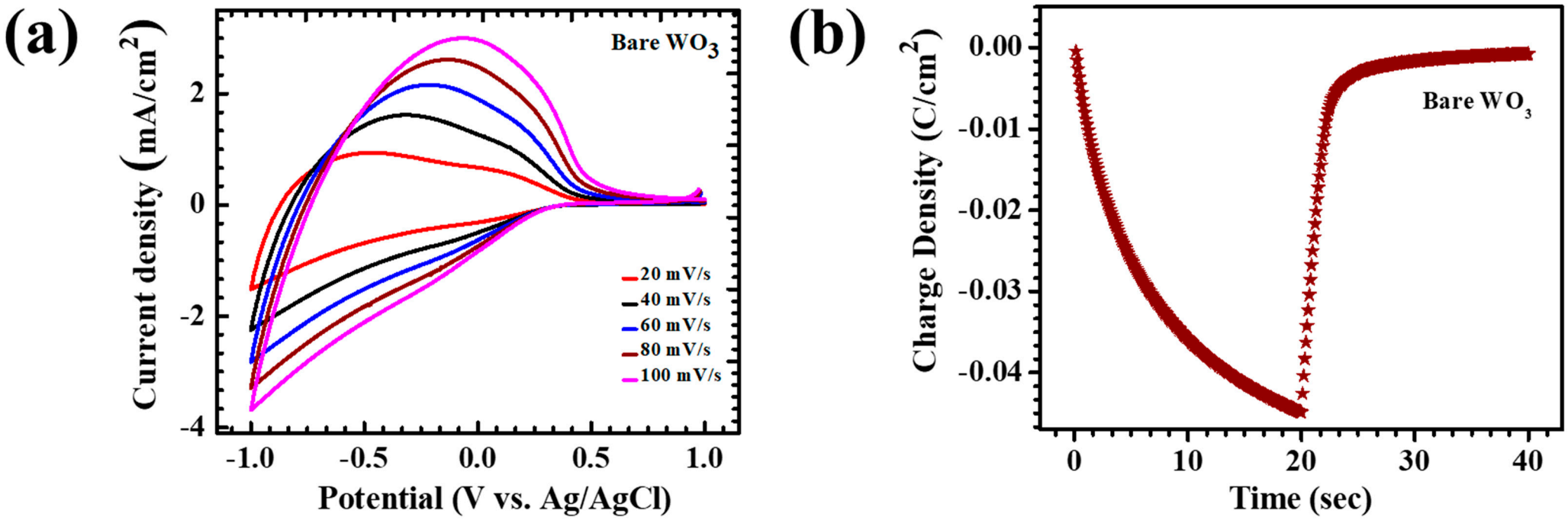

(a)
Bare WO3
20 mV/s
40 mV/s
60 mV/s
80 mV/s
100 mV/s
Current density (mA/cm2)
Potential (V vs. Ag/AgCl)
2
0
-2
-4
-1.0
-0.5
0.0
0.5
1.0
(b)
Bare WO3
Charge Density (C/cm2)
Time (sec)
0.00
-0.01
-0.02
-0.03
-0.04
0
10
20
30
40

Figure S1

Number	Deposition Technique	Temperature Range	Morphology	Reversibility (%)	Optical Modulation (ΔT_{600nm}%)	Coloration Efficiency (cm^2/C)	Reference
1.	Electrodeposition Technique	60° C	Nanograins	-	65.9	64.1	49
2.	Radio Frequency Sputtering	299.85 ° C (573 K)	Cracks Formation	-	-	52.38	50
3.	Electrodeposition Technique	100° C	Nanograins	-	68	62	15
4.	Radio Frequency Sputtering	200° C	Nanoplates	-	58	28.64	18
5.	**Electrodeposition Technique**	**250° C**	**Nanogranules**	**99**	**79.35**	**97.91**	**This Work**

Table S1